

Characterization of Electron Bunches in Ultrafast Electron Diffraction Beamlines at KAERI



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Application of Time-resolved Electron and X-ray Diffraction

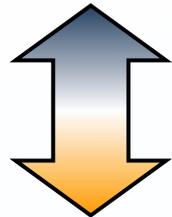
Gas, surface, thin film (Disordered media)

Electron

Coulomb
scattering

High scattering
power

Short penetration
depth



Mutually complementary tools

X-ray

Thomson
scattering

Low scattering
power

Long penetration
depth

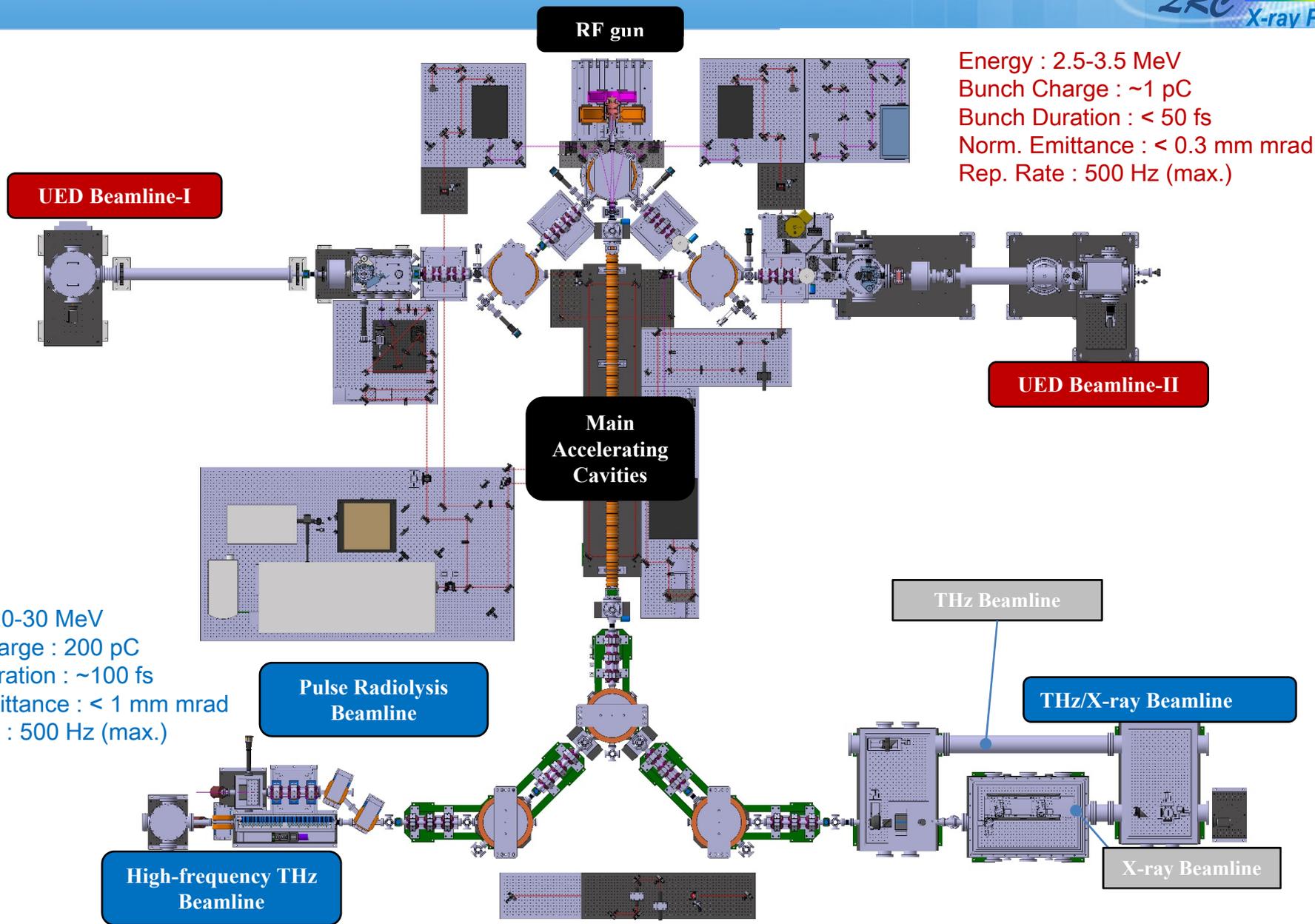
Solution, crystal (Ordered media)

X-FEL vs. UED



	X-FEL	UED
Source	X-ray	Electron
Wavelength	10-0.1 nm	0.1-0.001 nm
Interaction with	Electrons	Nuclei & Electrons
Scattering Power	Low	High
Penetration Depth	High	Low
Minimum Photon/Particle Numbers for Single-shot Measurement	10^{12} photons	10^6 electrons
Facility Size	Huge (~ km)	Compact (~ m)
Coherence Length	A few mm	A few nm

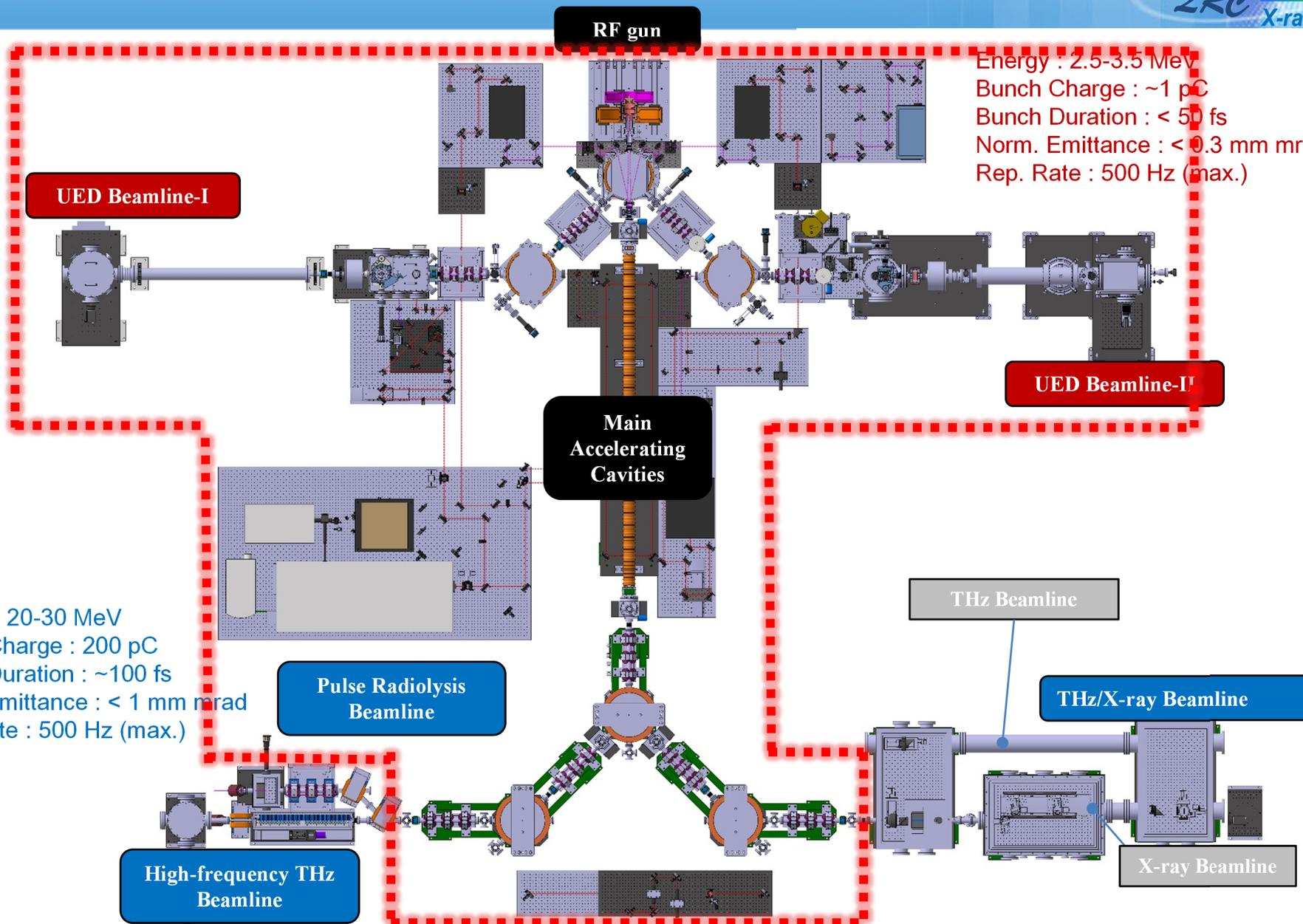
Accelerator Facility Overview



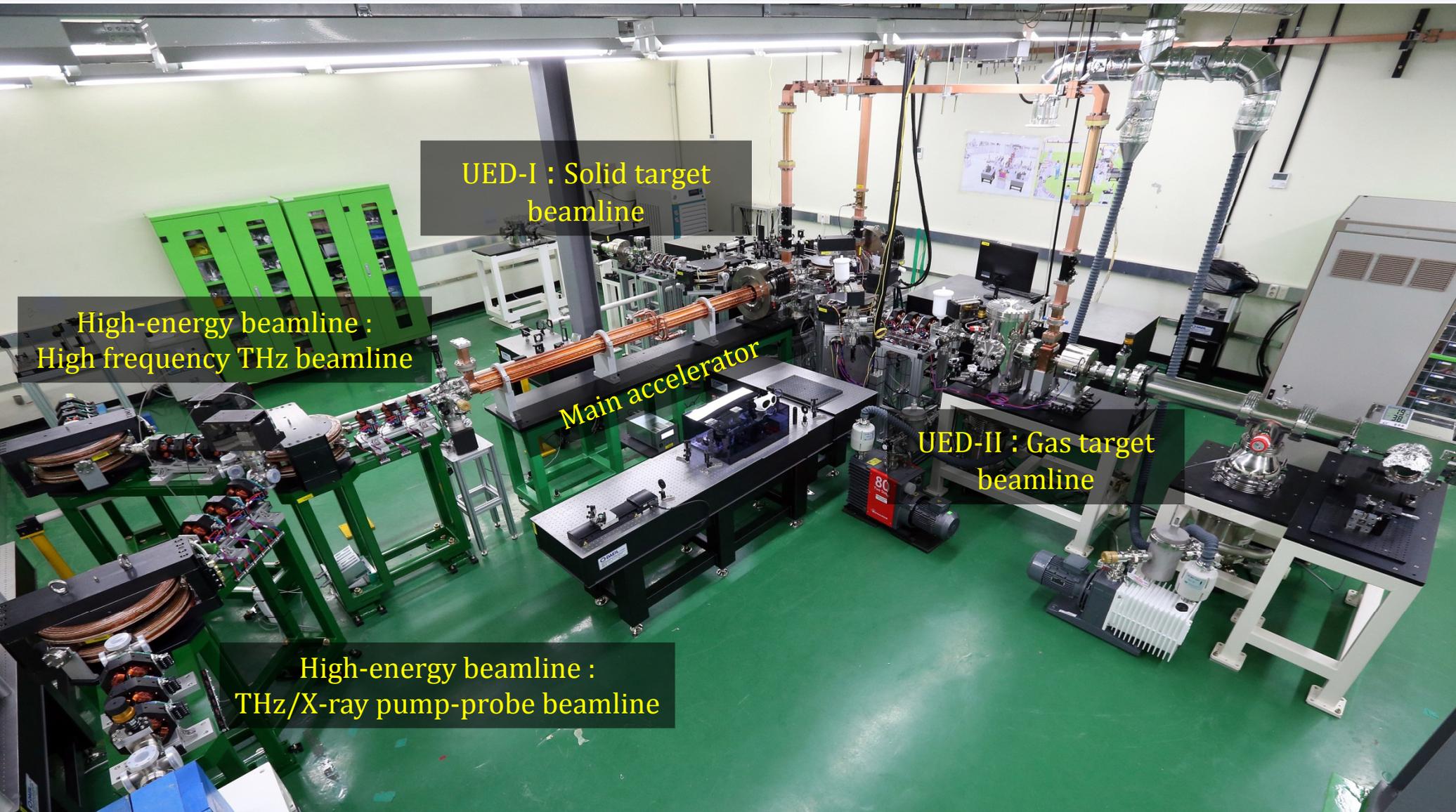
Accelerator Facility Overview

Energy : 2.5-3.5 MeV
Bunch Charge : ~1 pC
Bunch Duration : < 50 fs
Norm. Emittance : < 0.3 mm mrad
Rep. Rate : 500 Hz (max.)

Energy : 20-30 MeV
Bunch Charge : 200 pC
Bunch Duration : ~100 fs
Norm. Emittance : < 1 mm mrad
Rep. Rate : 500 Hz (max.)



Current Beamline



UED-I : Solid target beamline

High-energy beamline :
High frequency THz beamline

Main accelerator

UED-II : Gas target beamline

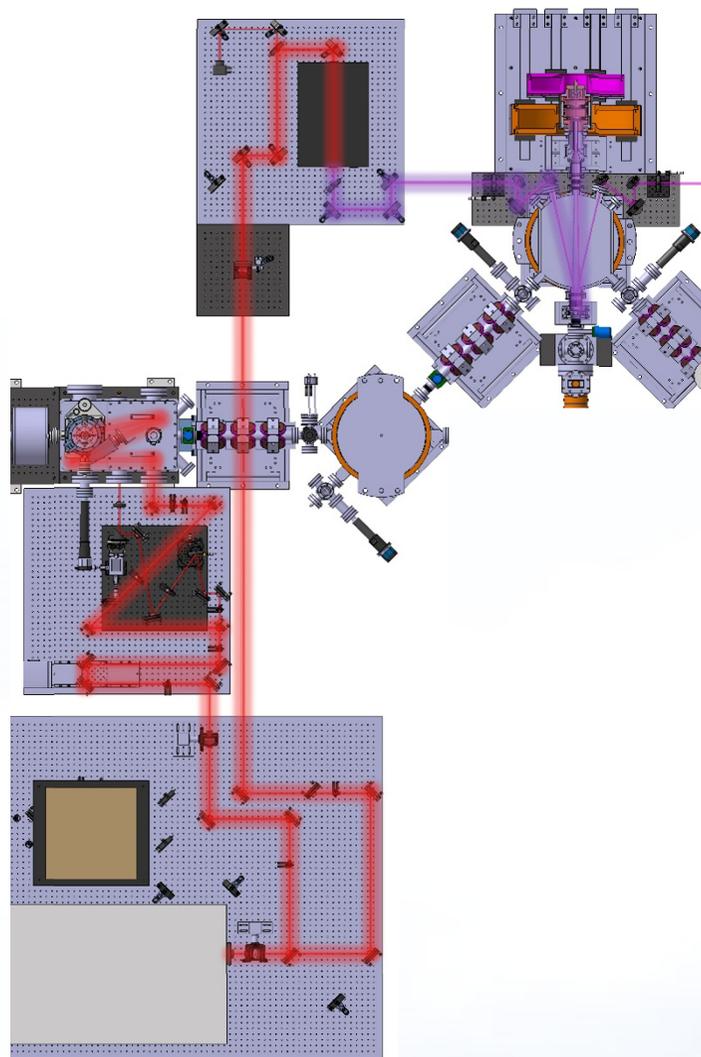
High-energy beamline :
THz/X-ray pump-probe beamline

Target Beam Parameters of UED Beamlines



Beam parameters	Target	Simulation	Units
Laser spot size@cathode (FWHM)	< 1	0.5	mm
Laser pulse length@cathode (FWHM)	< 200	130	fs
Bunch charge	> 0.16	1	pC
Beam kinetic energy	~3	3	MeV
Energy spread (rms)	< 0.3	0.17	%
Normalized emittance	< 0.3	0.29	mm mrad
Bunch length (rms)	< 50	32	fs
Timing jitter	< 50	13	fs

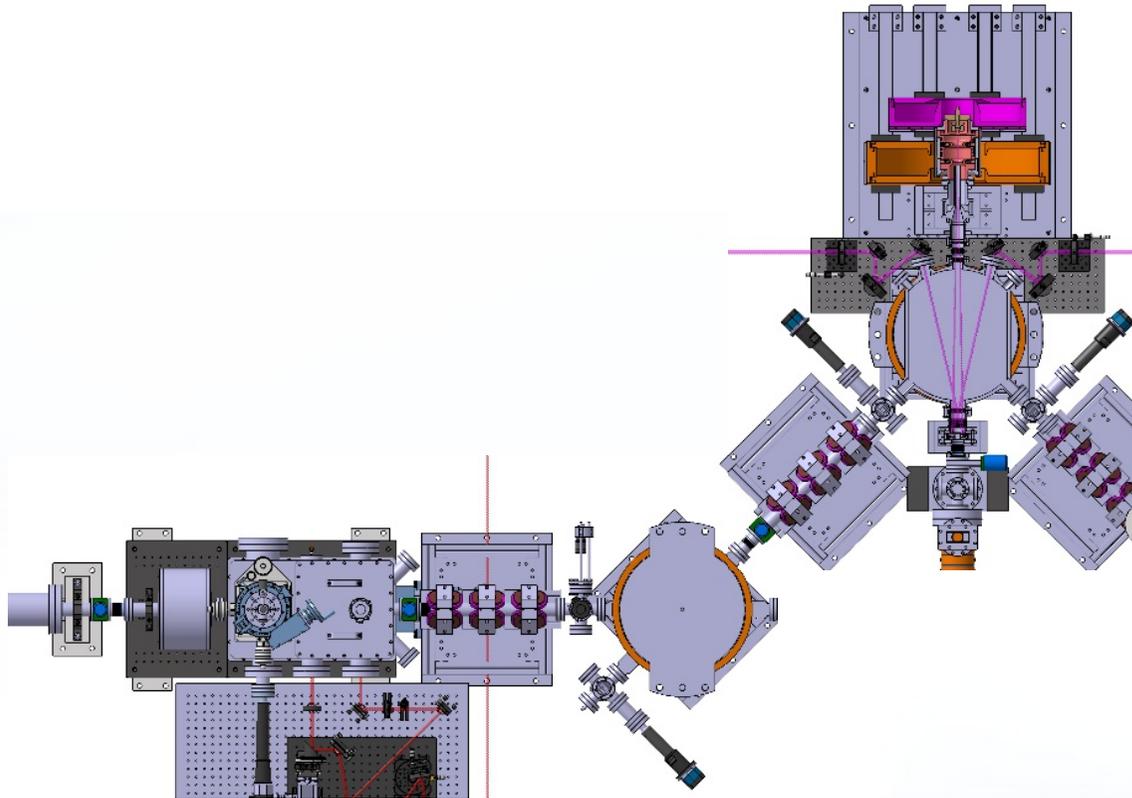
90-degree Bending Structure



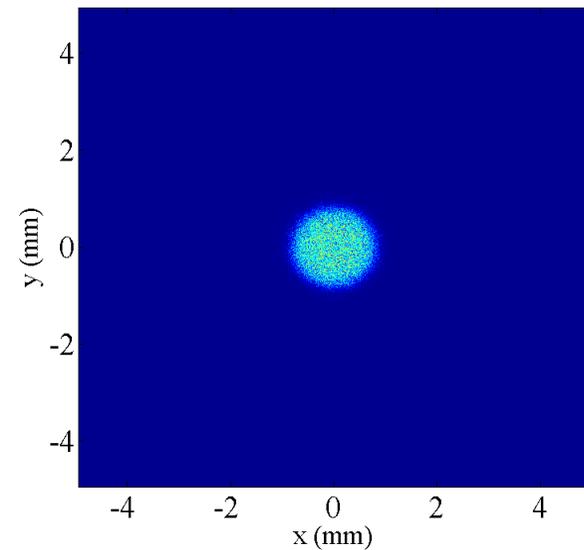
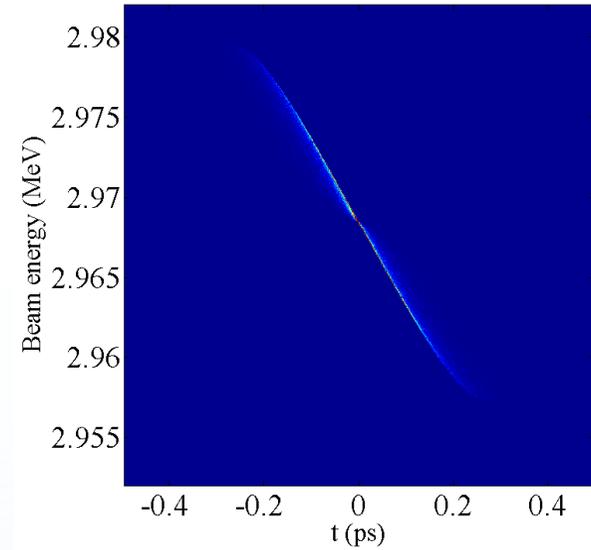
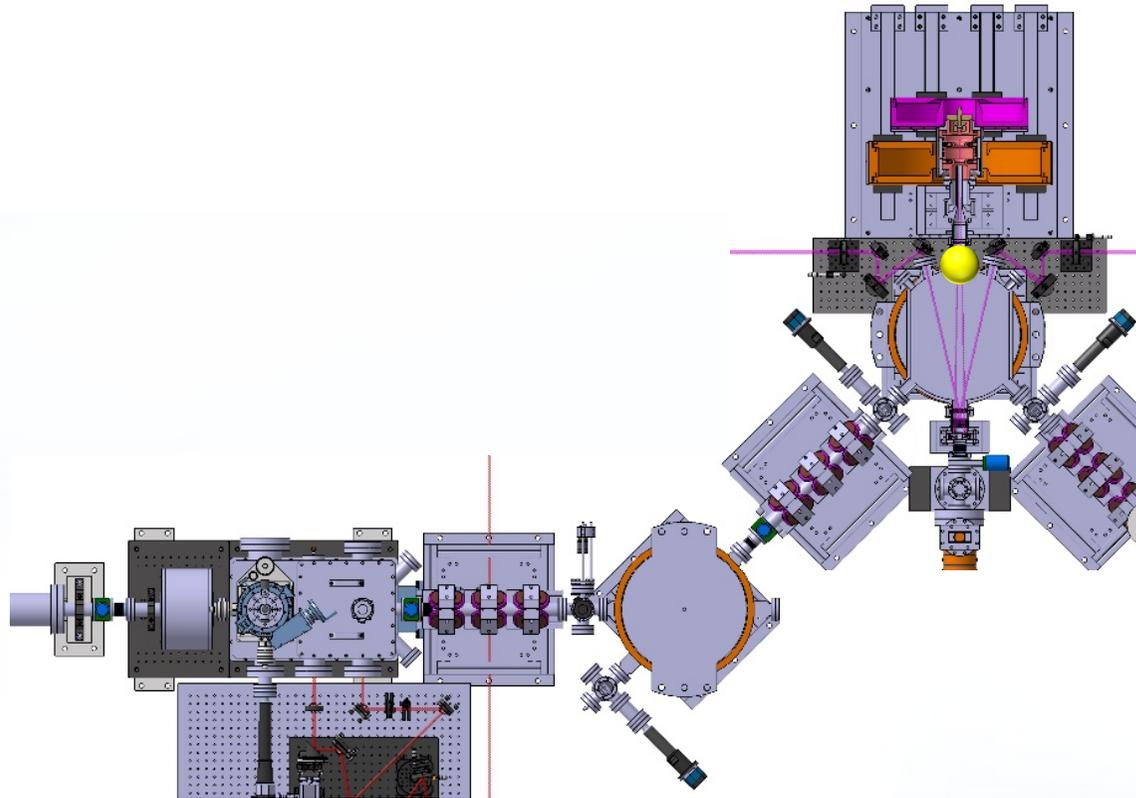
Beam parameters	Target	Units
Number of electrons	$> 1.0 \times 10^6$	electrons
Normalized emittance	< 0.3	mm mrad
Bunch length (rms)	< 50	fs
Timing jitter (rms)	< 50	fs

- Single shot measurement
- High temporal-spatial resolution

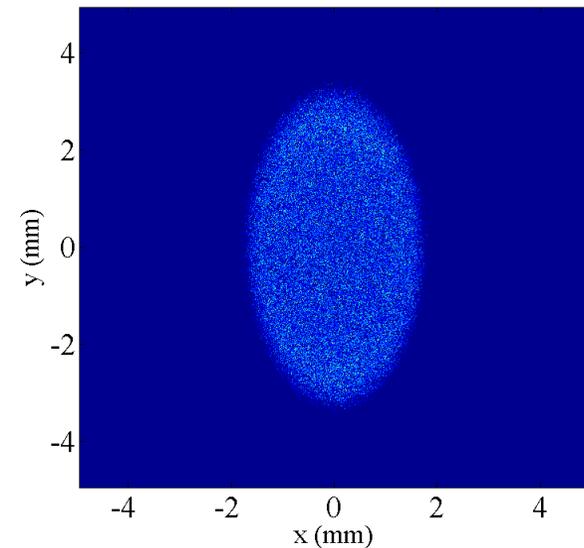
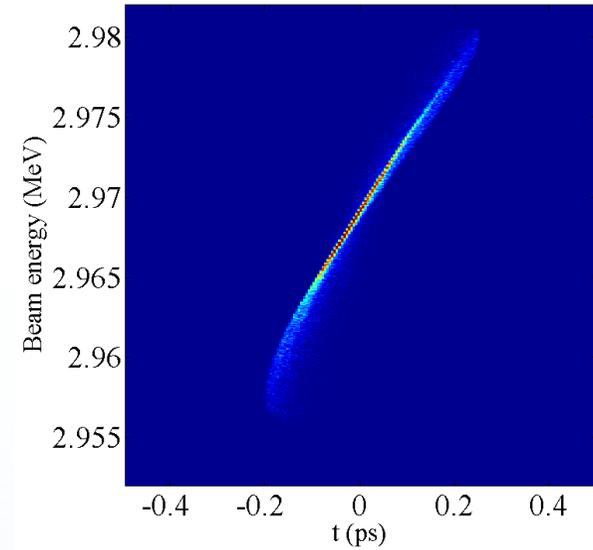
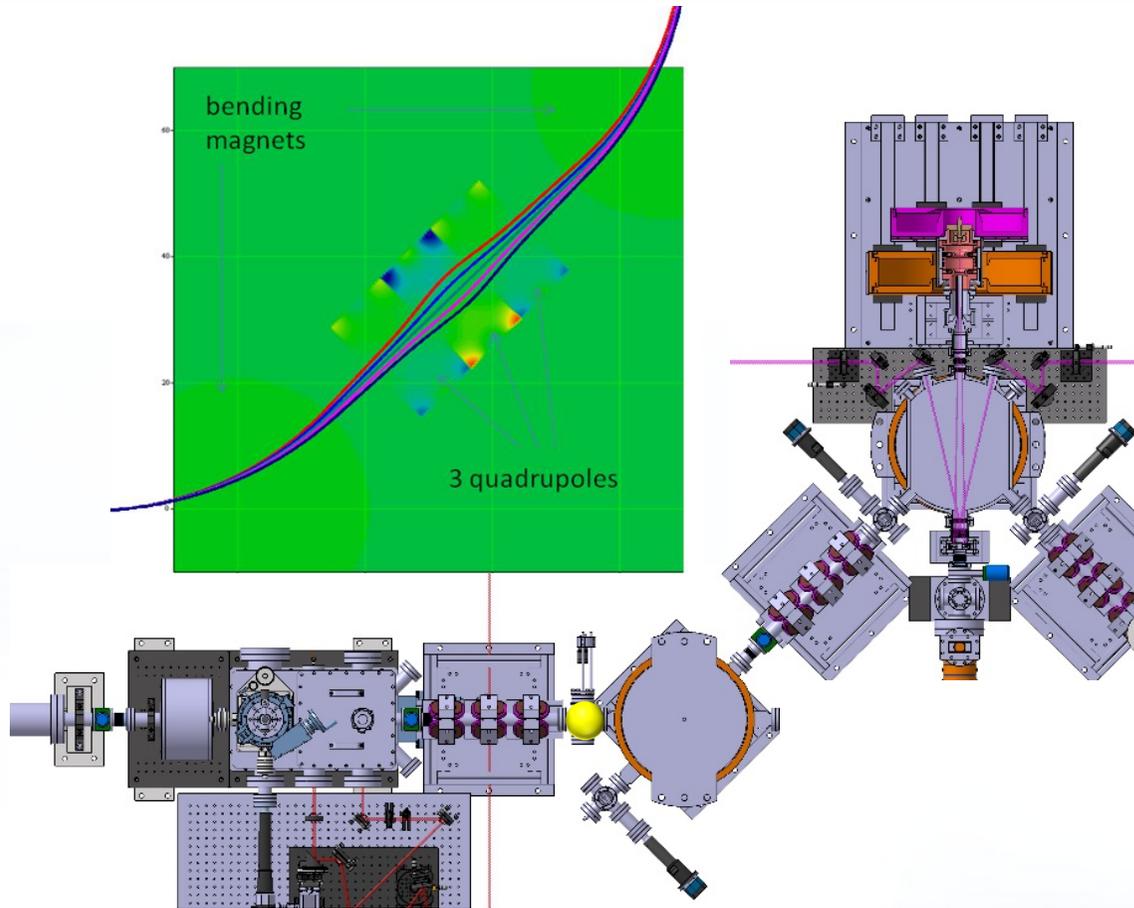
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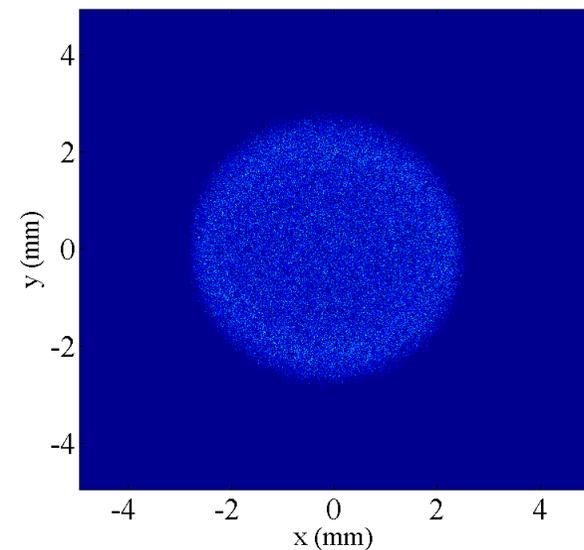
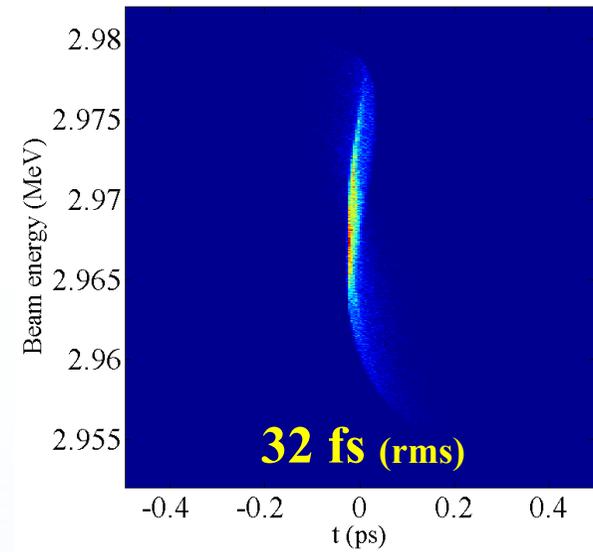
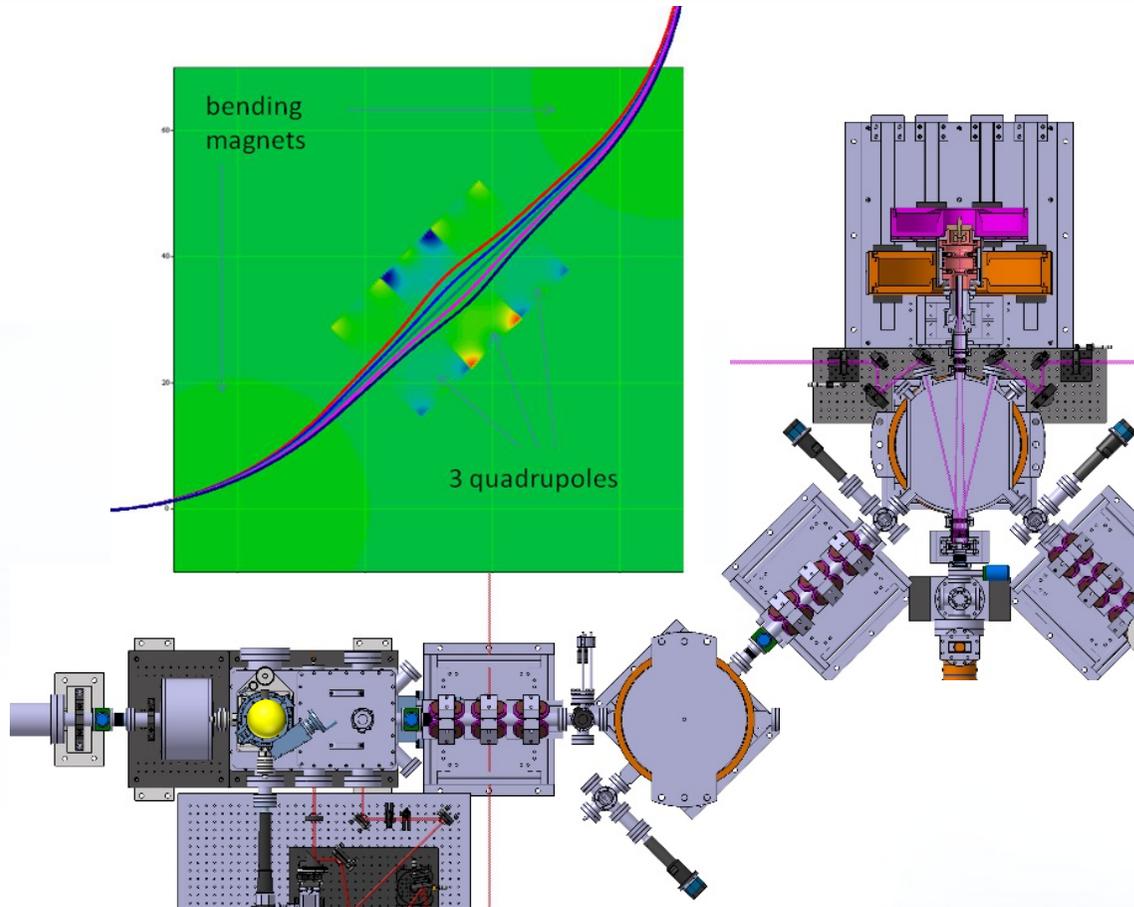
90-degree Bending Structure



90-degree Bending Structure



90-degree Bending Structure



Main Factor of Timing Fluctuation



1. Timing Fluctuation by RF gun Temperature

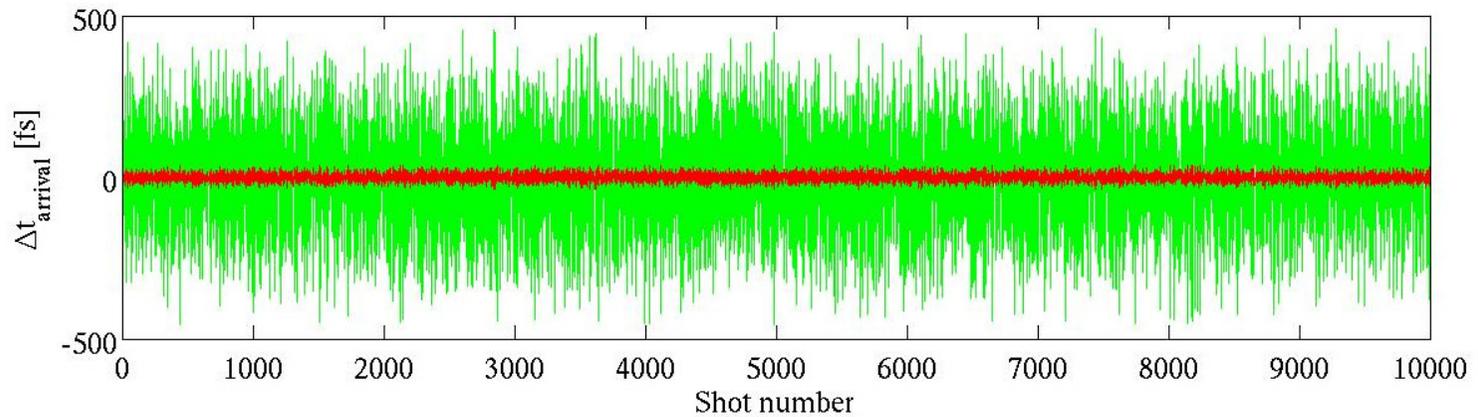
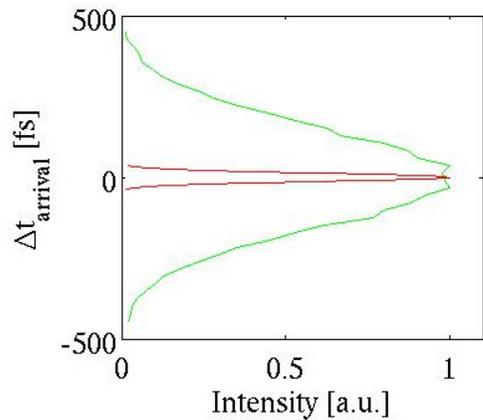
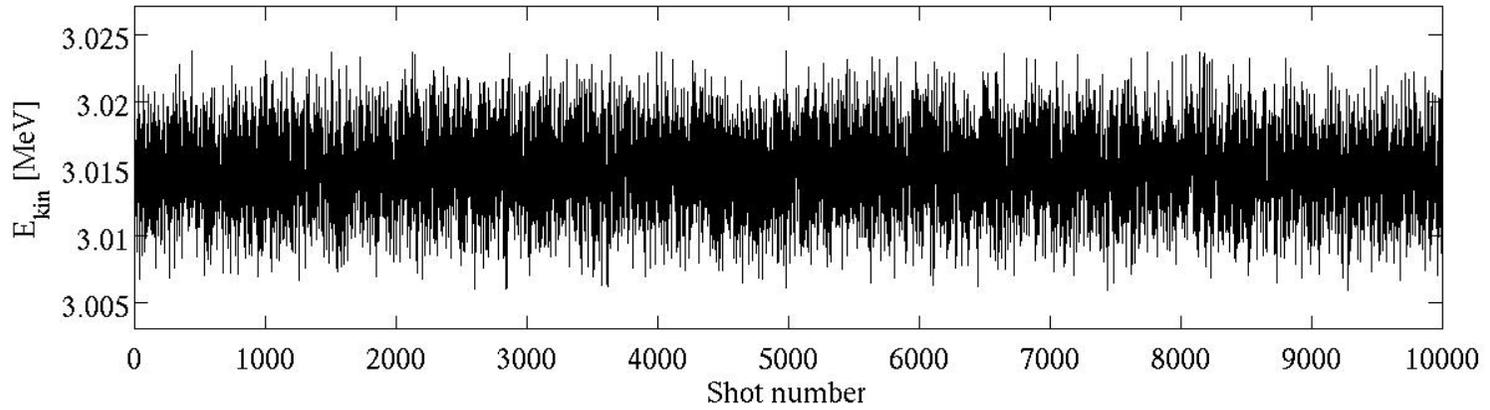
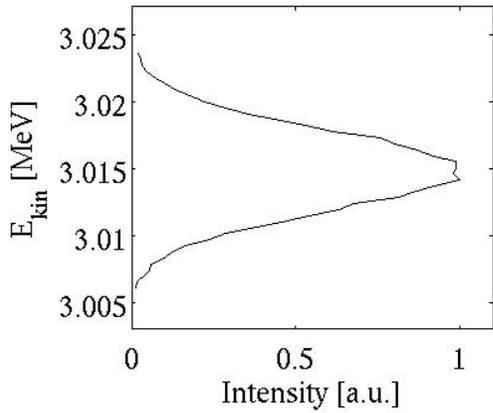
- Injection Phase Fluctuation
- Electron Energy Fluctuation

2. RF Amplitude Fluctuation : $< 10^{-4}$

3. Timing Fluctuation between Laser Pulses and RF Phase

- RF Master Oscillator v.s Laser Oscillator : 10 fs
- RF Master Oscillator v.s Klystron : 20 fs
- RF Travelling from Klystron to Photogun
- Laser Travelling from Regen. Amplifier to Photogun

Timing Stability of Electron Beam



Δt_{jitter} (rms)
3 m with 90-degree bend = 13 fs 3 m straight line = 152 fs

RF Phase and Amplitude Change by Temperature



Phase fluctuation due to cavity temperature change.

$$\Delta\varphi \cong 2\alpha Q_L \Delta T \quad \alpha : \text{linear thermal expansion coefficient, } 16.668 \times 10^{-6}$$

Q_L : Loaded quality factor, 7398

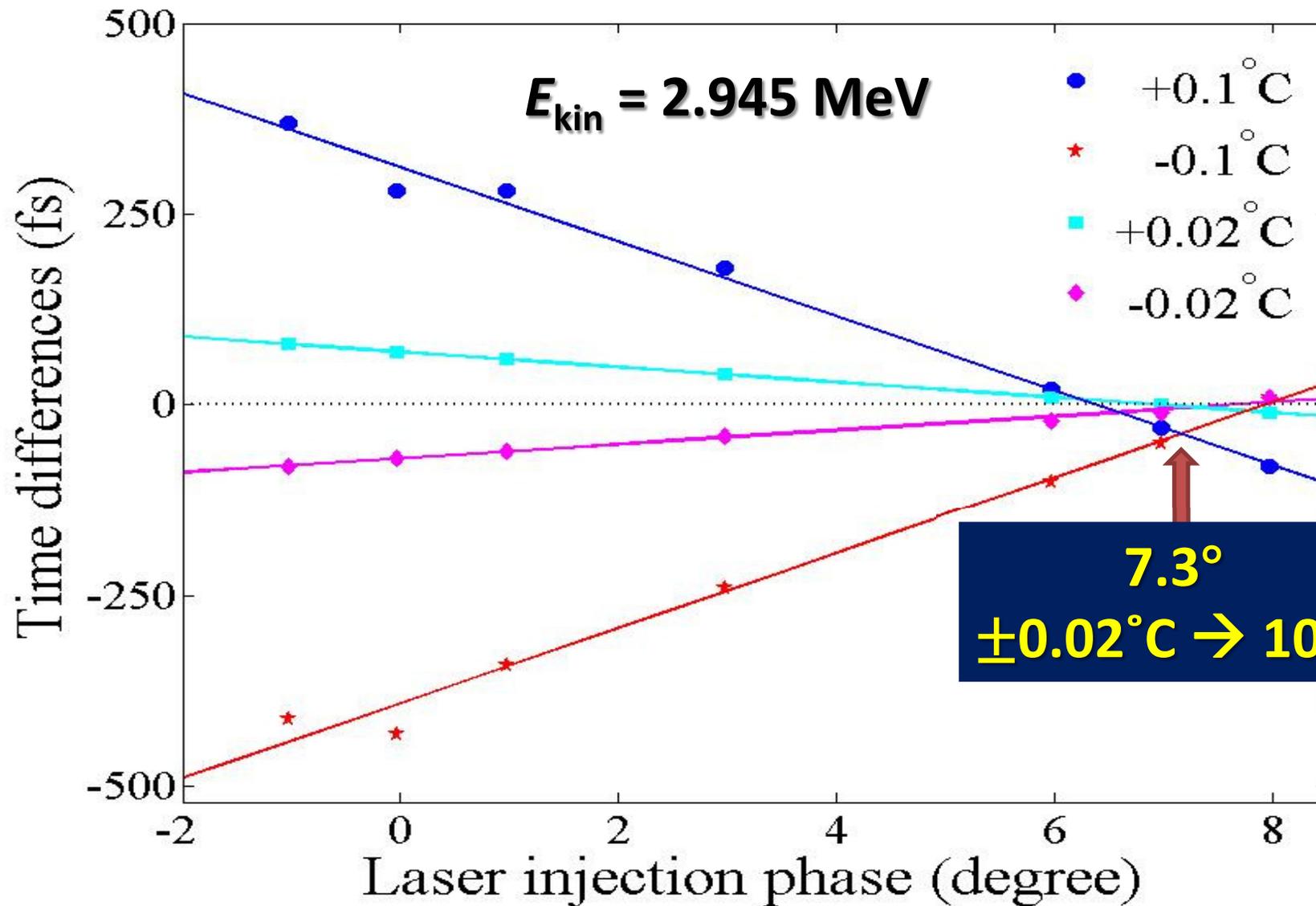
ΔT : Temperature change

$$\text{If } \Delta T = \pm 0.02^\circ\text{C}, \Delta\varphi \sim \pm 0.28^\circ$$

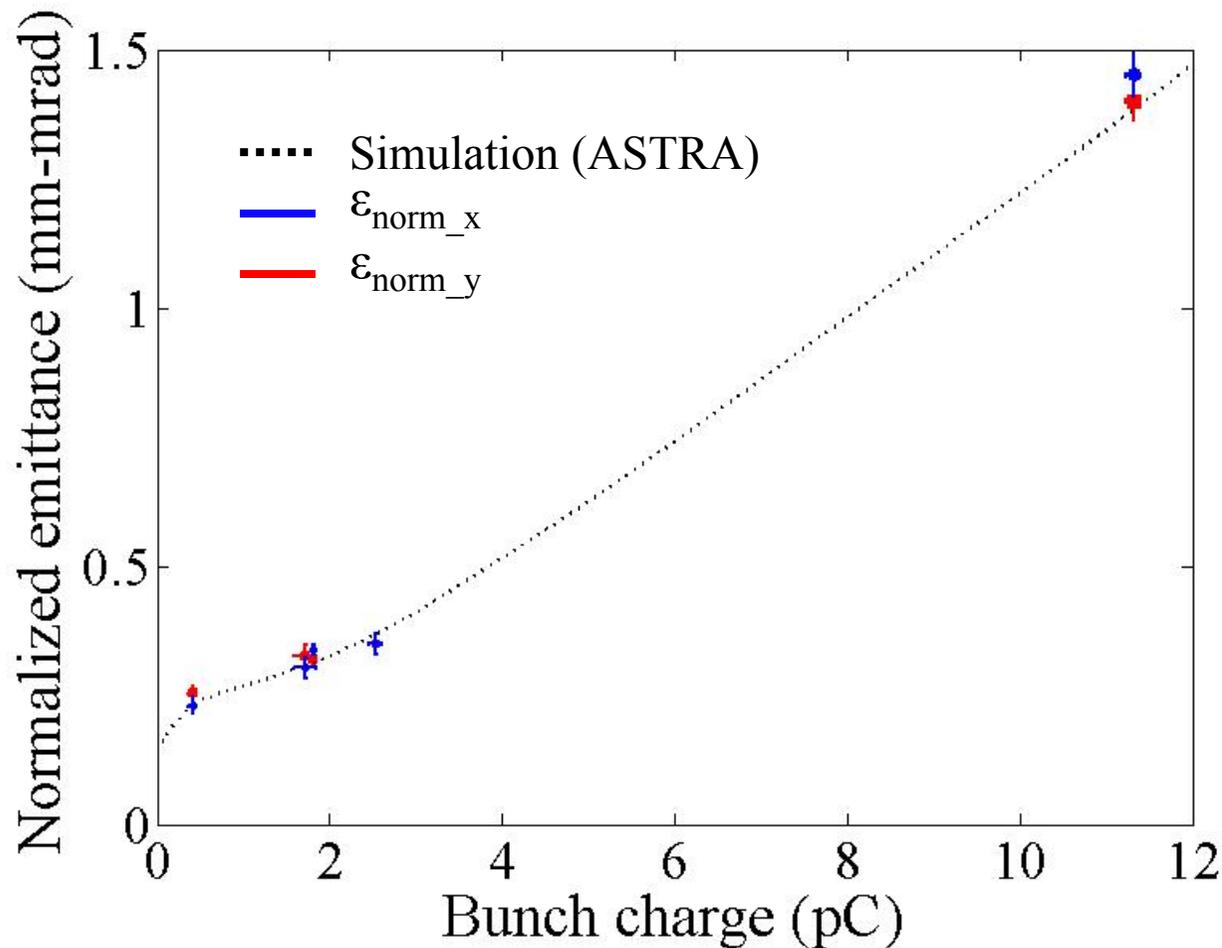
Voltage fluctuation due to cavity temperature change.

$$\frac{\Delta V}{V} \cong \frac{(\Delta\varphi)^2}{2} \quad \text{If } \Delta T = \pm 0.02^\circ\text{C}, \frac{\Delta V}{V} \sim \pm 1.2 \times 10^{-5}$$

Timing Fluctuation by RF gun Temperature



Emittance Measurement



Parameters	
Laser spot size @cathode	200 μm FWHM
Bunch charge	0.4 – 11.3 pC
Beam energy	3 MeV
ϵ_{norm_x}	0.23 – 1.45 mm-mrad
ϵ_{norm_y}	0.25 - 1.40 mm-mrad

Main Factor of Timing Fluctuation



1. Timing Fluctuation by RF gun Temperature

- Injection Phase Fluctuation
- Electron Energy Fluctuation

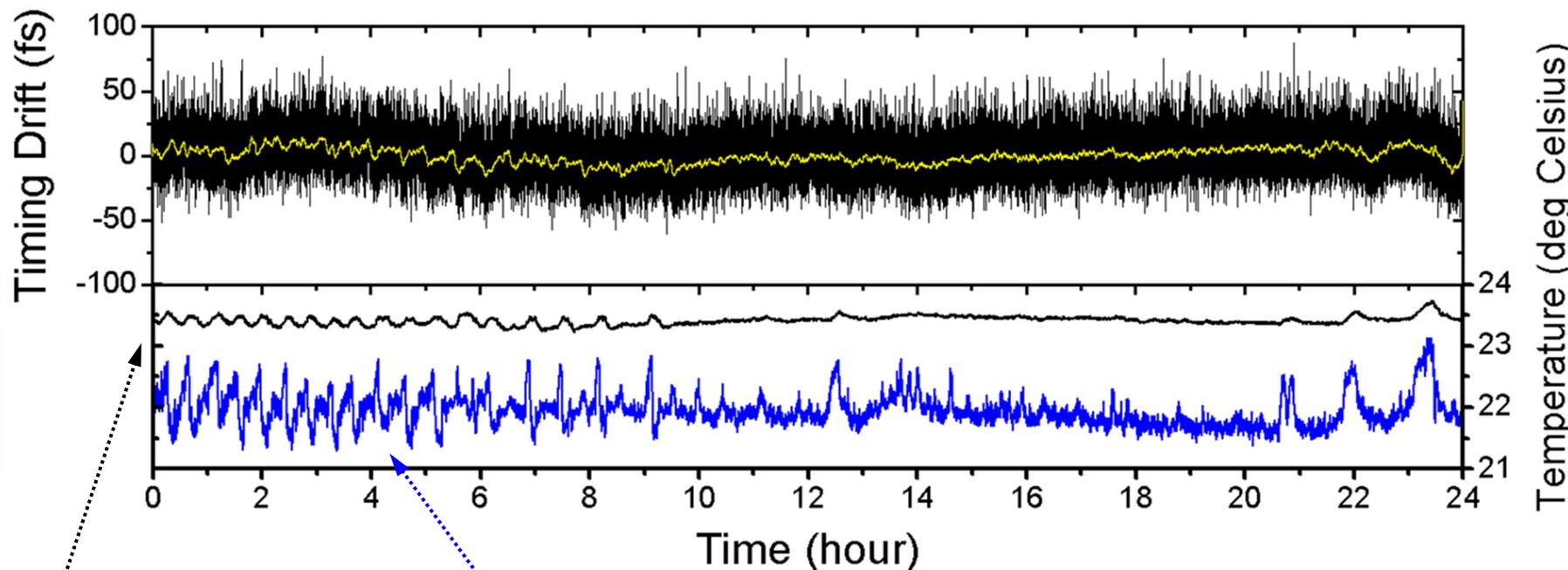
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- Laser Travelling from Regen. Amplifier to Photogun

RF-laser Timing Synchronization

12.5 fs rms stability maintained over 24 hours



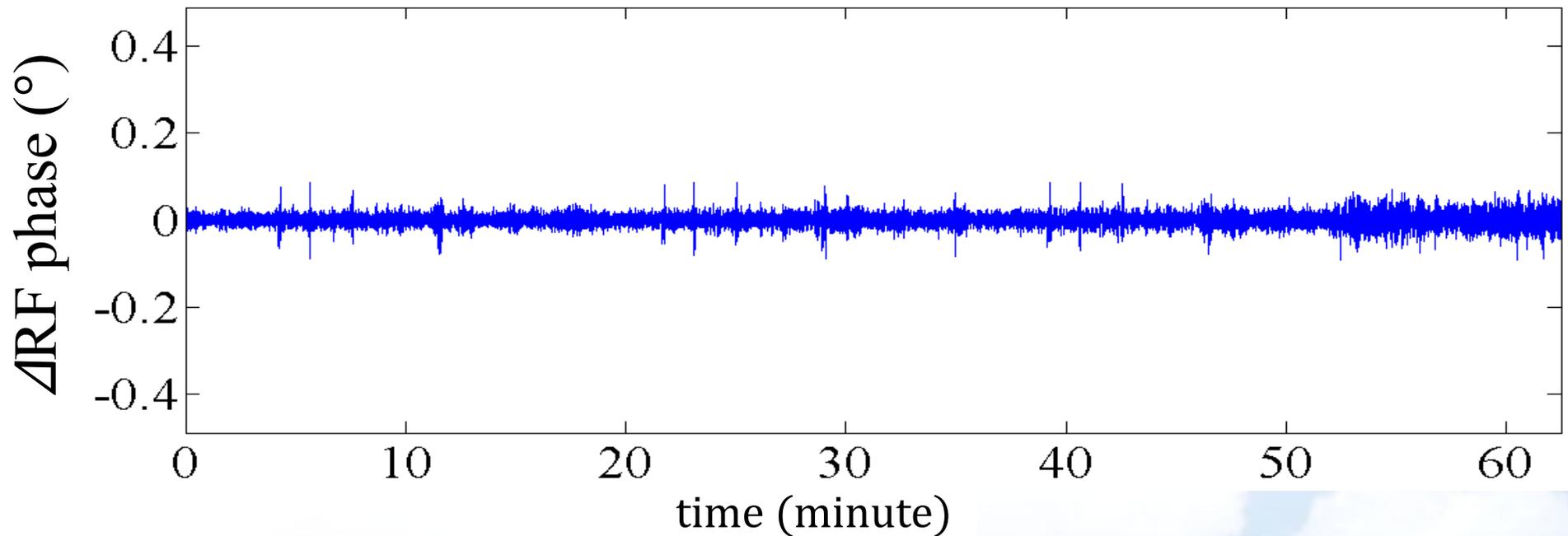
FLOM-PD box
temperature
(water-cooling)

Laboratory
temperature

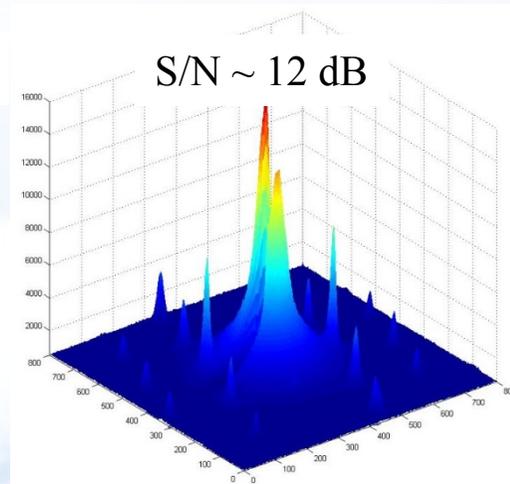
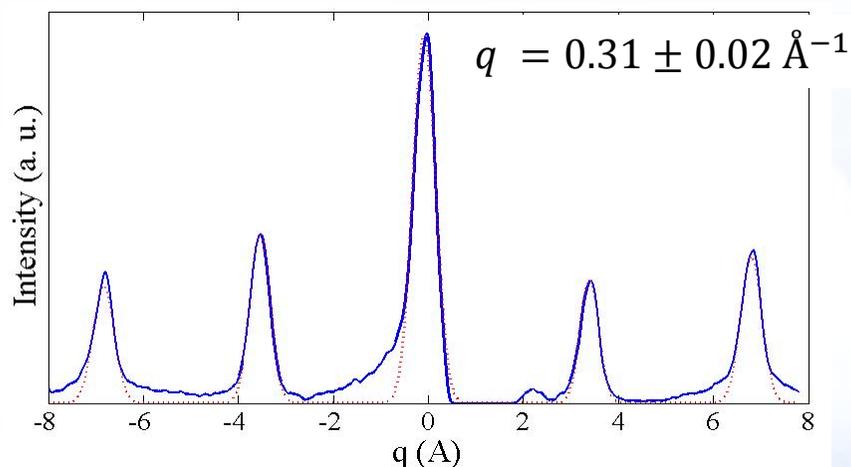
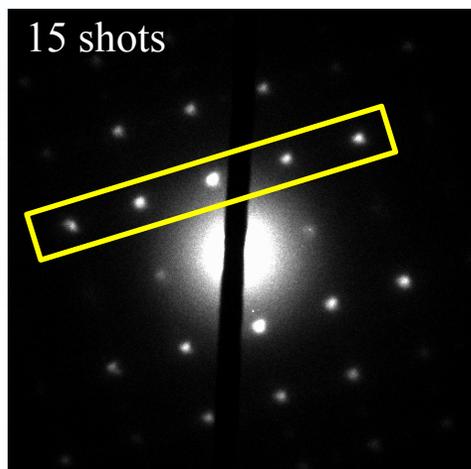
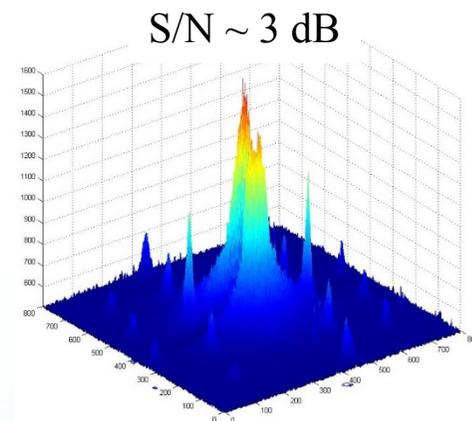
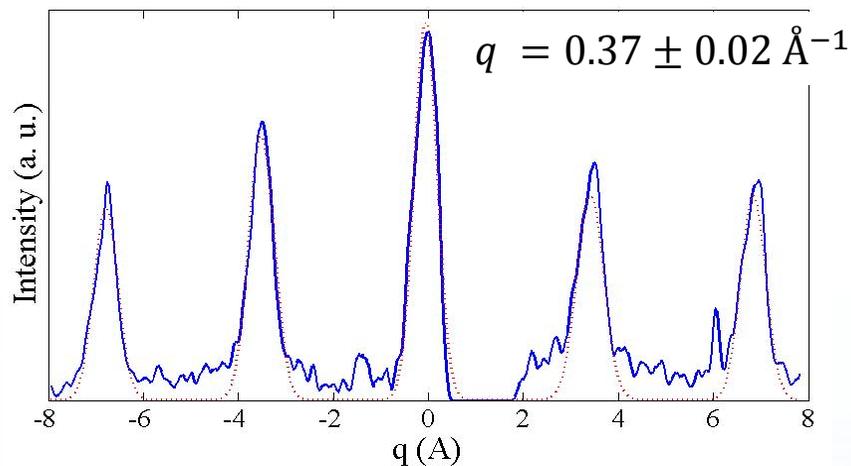
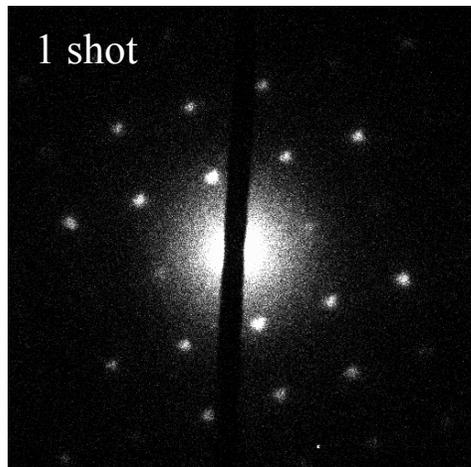
H. Yang et al, "10-fs-level synchronization of photocathode laser with RF-oscillator for ultrafast electron and X-ray sources," Sci. Rep. 7, 39966 (2017)

Phase Fluctuation of the RF gun

RF phase fluctuation 0.017 deg (16.8 fs) rms



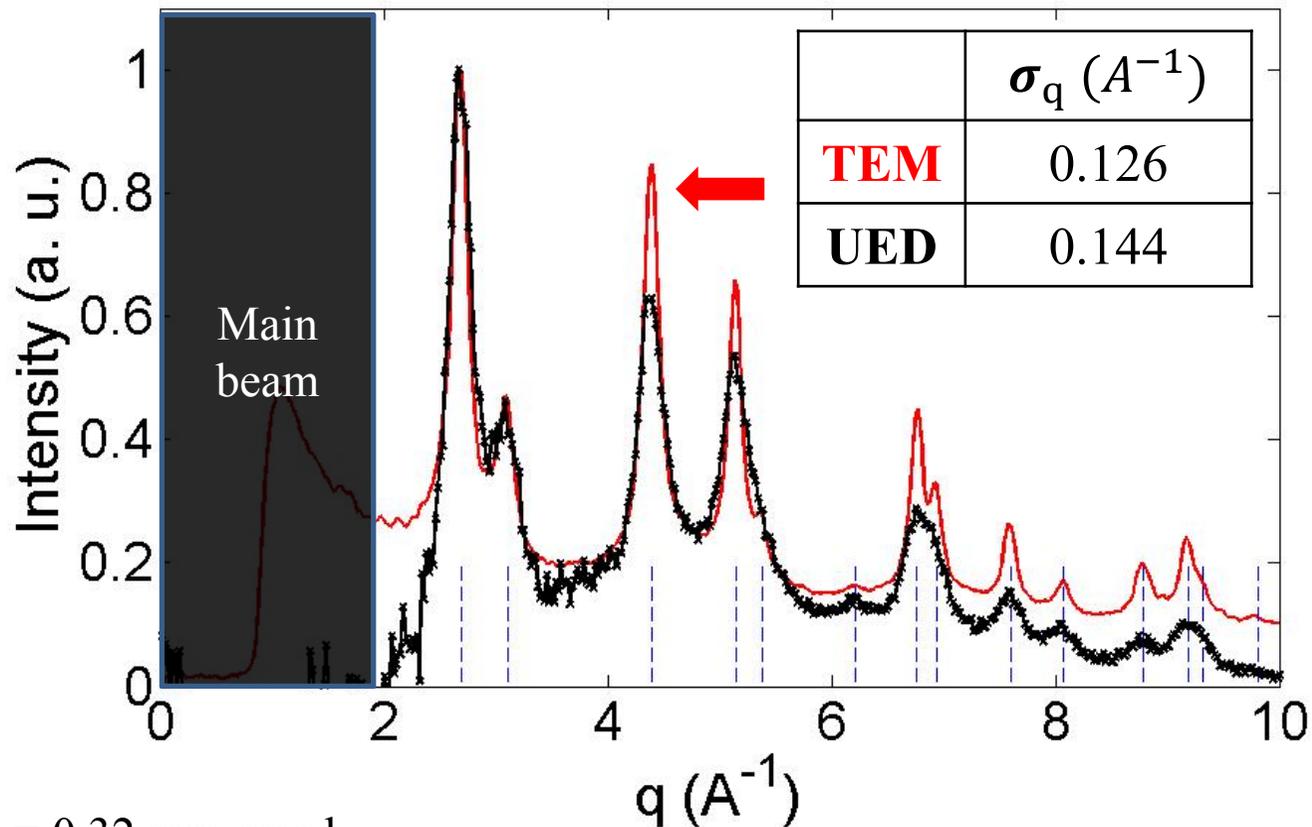
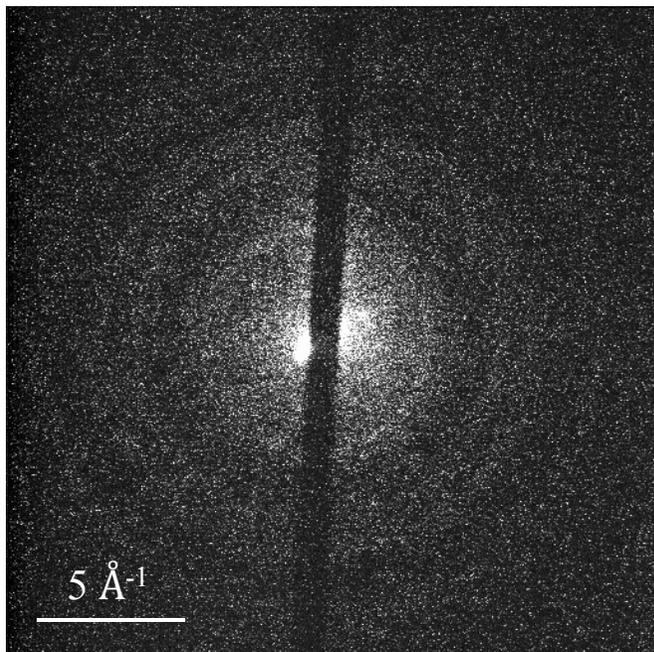
Electron Diffraction Image of Single-crystal Si



Silicon thin film

- ❖ Single-crystalline
- ❖ Film thickness of 200 nm

Electron Diffraction Image of Poly-crystal Au



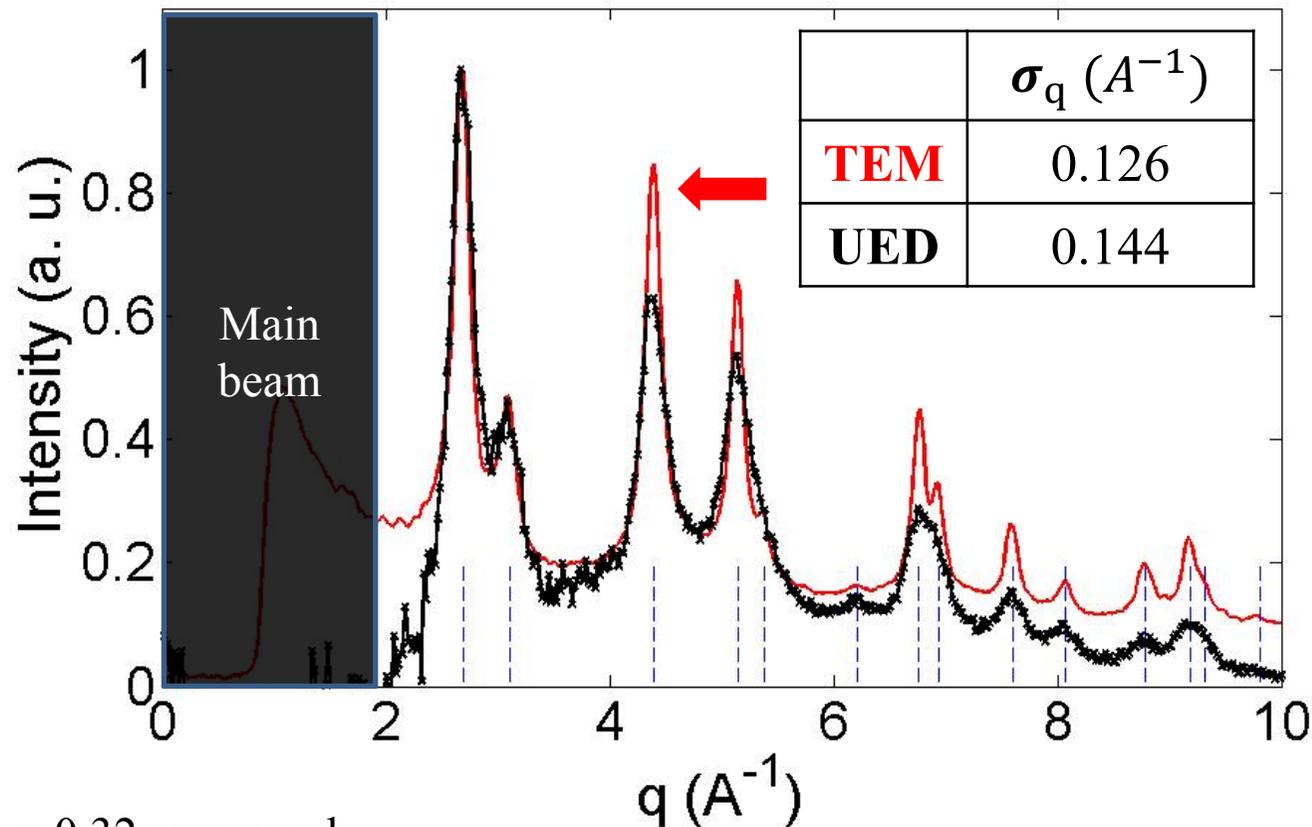
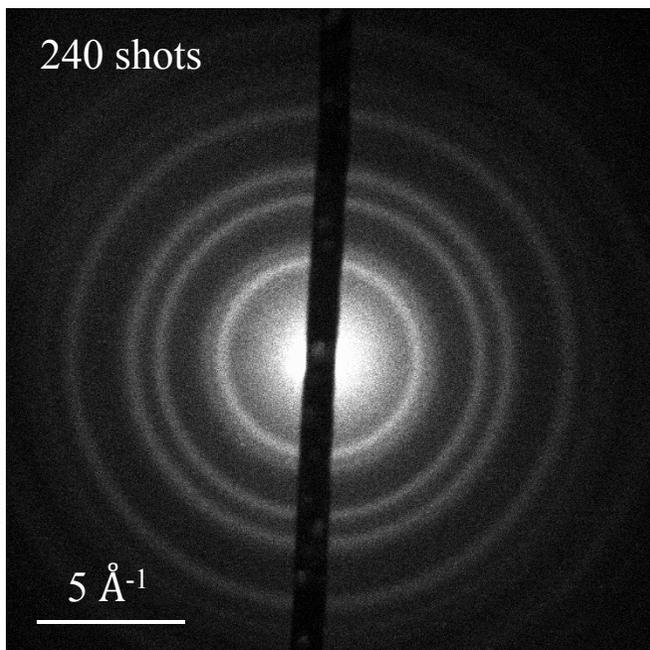
Beam parameters

$Q = 1.8$ pC, $E_k = 2.75$ MeV, $\epsilon_n = 0.32$ mm-mrad

Gold thin film

- ❖ Poly-crystalline
- ❖ Film thickness of 50 nm

Electron Diffraction Image of Poly-crystal Au



▪ Beam parameters

$Q = 1.8$ pC, $E_k = 2.75$ MeV, $\epsilon_n = 0.32$ mm-mrad

Gold thin film

- ❖ Poly-crystalline
- ❖ Film thickness of 50 nm

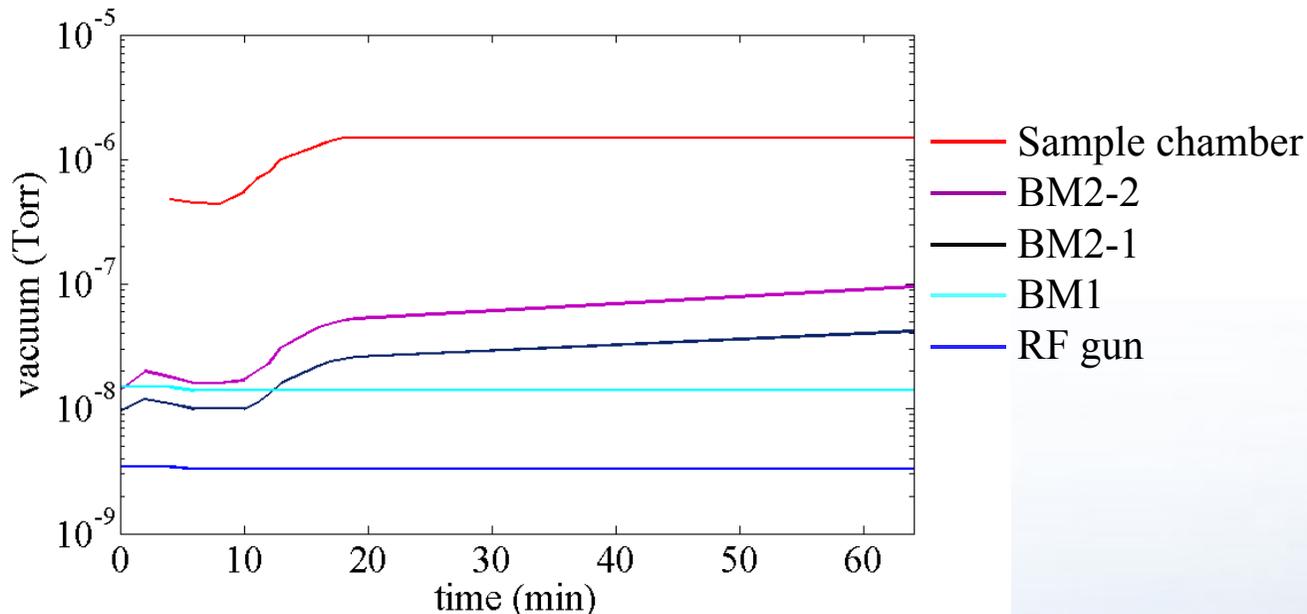
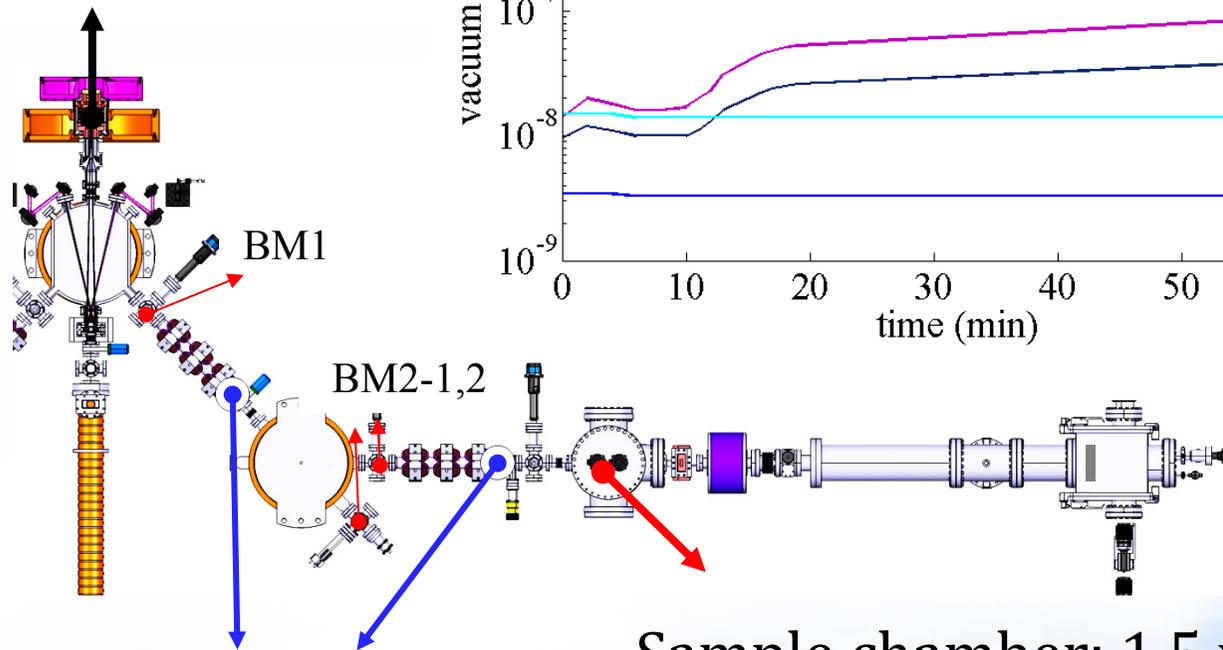
Beam Parameters



Beam parameters	Simulation	Measurement	Units
Laser spot size@cathode (FWHM)	0.5	0.2-0.5	mm
Laser pulse length@cathode (FWHM)	130	130	fs
Bunch charge	1	0.4-2.5	pC
Beam kinetic energy	3	2.8-3	MeV
Energy spread (rms)	0.17	~ 0.23	%
Normalized emittance	0.29	0.23-0.34	mm mrad
Bunch length (rms)	32	-	fs
Timing jitter	13	-	fs

Differential Pumping for Gas Sample

RF gun : 3.3×10^{-9} Torr



Sample chamber: 1.5×10^{-6} Torr

Pipe for differential pumping

- R = 5 mm
- L = 50 cm
- Liquid nitrogen cold trap

Summary



- 90-degree bending structure is expected to reduce bunch length and timing jitter.
- Measured beam parameters are in good agreement with simulation.
- Bunch length measurement : transverse deflecting cavity or Michelson interferometer using CTR generated by electron beam.
- Timing jitter measurement : transverse deflecting cavity spectral decoding or laser-induced ponderomotive deflecting .
- Bismuth samples are being prepared to measure temporal resolution.

TUP046 - Ultrafast Electron Diffraction Facility Based on an RF Photogun and Achromatic 90-degree Bends for Sub-100-Femtosecond Timing Jitter

TUP047 - A Linac-Based All-in-One THz-Pump and X-Ray-Probe Sources

WEP013 - Photocathode RF Gun Development at KAERI for Time-Resolving Pump / Probe System

WEP035 - Measurements of Electron Bunch Timing Jitter Using Spectral Decoding Technique for Ultrafast Electron Diffraction Experiments

WEP059 – Development of T-Ray-Pumped Ultrafast Electron Diffraction Beamline

Thank you for your kind attention.